

Form PTO-1449 COMMERCE (REV. 7-80)		U.S. DEPARTMENT OF PATENT AND TRADEMARK OFFICE		DOCKET NO. N1 000771		Serial No.								
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				Applicant Rene Monshouwer et al										
				Filing Date Concurrently		Group								
U.S. PATENT DOCUMENTS														
Ex. Int.		Document Number							Date	Name	Class	Sub-class	Filing Date If Approp.	
120	AA	4	7	3	7	8	2	3	4/12/88	Bouwer et al	355	53	10/14/86	
120	AB	5	0	2	6	1	6	6	6/25/91	Van der Werf	356	401	10/1/84	
120	AC	5	1	9	1	2	0	0	3/2/93	Van der Werf	250	201	12/16/91	
120	AD	4	3	5	6	3	9	2	10/26/82	Wittekoek et al	250	201	6/11/80	
120	AE	4	8	6	1	1	6	2	8/29/89	Ina et al	356	401	11/15/88	
120	AF	5	4	1	4	5	1	4	5/9/95	Smith et al	356	363	6/1/93	
120	AG	4	7	7	8	2	7	5	10/18/88	Van den Brink	356	401	9/24/86	
120	AH	4	2	5	1	1	6	0	2/17/81	Bouwhuis et al	356	401	7/13/78	
120	AI	5	2	4	3	1	9	5	9/7/93	Nishi	250	548	12/29/92	
FOREIGN PATENT DOCUMENTS														
		Document Number							Date	Country	Class	Sub-Class	Trans.	
													Yes	No
120	AJ	0	4	9	8	4	9	9 A 1	8/12/92	Europe			X	
120	AK	9	8	3	9	6	8	9 A 1	9/11/98	World			X	
OTHER (Including Author, Title, Date, Pertinent Pages, Etc.)														
120	AL	"Submicrometer Lithographic Alignment and Overlay Strategies", by Saleem H. Zaidi et al, SPIE Vol. 1343, 1990, pages 245-255.												
120	AM	"Overlay Accuracy Measurement Technique using the Latent Image on a Chemically Amplified Resist", by K. Yamashita et al., J. Appl. Phys. Vol. 35, 1996, pages 56-60.												
120	AN	"Submicron 1:1 Optical Lithography", by David A. Markle, Semiconductor International May 1986.												
Examiner <i>Dan J. Smith</i>										Date Considered 6/9/04				